

ASML TWINSCAN NXT:1980* ArF Immersion Scanner

- Manufacturer: ASML
- Model: TWINSCAN NXT:1980
- Wafer Size: 300mm
- Track Interface: TEL Lithius
- CYMER XLR-660 193nm, 60W, 6kHz Laser Source
- 1.35NA Catadioptric Projection Lens with 4x Reduction
- Aerial XP Polarized illuminator
- Quasar XL illumination module
- Next Generation Magnetically Levitated Dual-Stage Technology delivering $\leq 2.5\text{nm}$ (chuck dedicated) single machine overlay
- Alignment System:
 - SMASH NXT Alignment System
- Advanced Lens Control X/Y
- Image Tuner
- Focus Spot monitoring
- Polarization Control
- CD-FEC
- LS MATCH2
- Reticle System:
 - Reticle error compensation
 - Reticle shape correction
 - Reticle management and E-connectivity support
- In-situ metrology (ILIAS)
- LITHOGUIDE (LIAS)
- DOSEMAPPER
- Athena Narrow Marks
- Inform (SECS)
- User interface UNIX/SUN Architecture
- Additional information available upon request

Other Features:

- Azimuthal Polarization
- AUX Port 300mm FOUP/25 Wafer
- FOUP Lock-out system
- Universal Pre-alignment
- Chuck Dedication
- Integrated Reticle Library
- IRIS XT
- Reticle CIDRW Asyst (RF)
- 2D Barcode reader
- 24-char barcode reader twinscan
- PEP High Dose (60W)
- Agile for NXT
- Spotless NXT
- Exposure
- GRIDMAPPER
- GRIDMAPPER IF
- Green Laser Attenuation
- INFORM
- BASELINER
- BASELINER MMO Stability
- BMMO2
- InformPro
- InformPro2
- Overlay Optimizer FO
- Overlay Optimizer 2
- Water cooling for electronics cabinet
- 122mm Pellicle Frame Compatibility
- Reorder Lot Service
- Recipe Creator Light
- Soft Wafer Load
- Water Leak detection